

1 Inventor: Klaus F. Schuegraf

2 Title: Semiconductor Processing Methods of Chemical Vapor
3 Depositing SiO₂ on a Substrate

4 Assignee: Micron Technology, Inc.

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6 INFORMATION DISCLOSURE STATEMENT

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8 References -- See Attached Form PTO-1449

9 The attached form PTO-1449 is submitted in compliance
10 with 37 CFR §1.56. No admission is made regarding whether all the
11 submitted references are prior art.

12 Respectfully submitted,

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14 Dated: 12/15/98

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